



1. **Equipment & Model : AMAT P5000 CVD TEOS PLIS System**
2. **Manufacturer : Applied Materials Technology (AMAT)**
3. **Current Status : Deinstalled in Fully Working Condition in 2002**
4. **Wafer Size : 200mm**
5. **Process (Product) : PLIS TEOS SiO₂ CVD System**
6. **Hardware Configuration :**
 - 3 Dep. PLIS (Precision Liquid Injection System) Chamber
 - 1 Sputter Etch Chamber
 - Parts and Modules :
 - (1) 1-Delatech Scrubber Model 859(non-recirc)
 - (2) 1-Main power box w/4 ENI RF Generators
 - (3) 1-Delta RF generator rack w/3 RFPP generators
 - (4) 1-AMAT 'O' Heat exchanger
 - (5) 1-Front monitor
 - (6) 1-Rear monitor
 - (7) 3-50x20 Ebara pumps (Refurbished)
 - (8) 2-40x20 Ebara pumps (Refurbished)
 - (9) 1-Mini controller